

Title (en)
OPTICAL SUBSYSTEM, PARTICULARLY FOR A PROJECTION EXPOSURE SYSTEM COMPRISING AT LEAST ONE OPTICAL ELEMENT THAT CAN BE BROUGHT INTO AT LEAST TWO POSITIONS

Title (de)
OPTISCHES TEILSYSTEM INSBESONDERE FÜR EINE PROJEKTIONSBELICHTUNGSANLAGE MIT MINDESTENS EINEM IN MINDESTENS ZWEI STELLUNGEN VERBRINGBAREN OPTISCHEN ELEMENT

Title (fr)
SYSTEME PARTIEL OPTIQUE NOTAMMENT DESTINE A UN DISPOSITIF D'ECLAIRAGE DE PROJECTION COMPORTANT AU MOINS UN ELEMENT OPTIQUE POUVANT ETRE AMENE DANS AU MOINS DEUX POSITIONS

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Abstract (en)
[origin: WO2004021085A1] The invention relates to an optical subsystem, particularly for a projection exposure system for use in microlithography, having a pencil of rays (4) that passes through the optical subsystem, and having at least one optical element upon which the rays of the pencil of rays (4) impinge in a first area of use (12, 108.1, 152, 208.1, 308.1). The invention is characterized in that the optical element comprises at least one other area of use (14, 108.2, 154, 208.1, 308.1). The optical subsystem also comprises devices for bringing the optical element into at least two positions consisting of a first position and of a second/other position(s). In the first position, the pencil of rays impinges upon the surface of the optical element in the first area of use (12, 152, 108.1, 208.1, 308.1) and, in the second/other position(s), the pencil of rays impinges upon the surface of the optical element in a second/other area of use (14, 154, 108.2, 208.2, 308.2).

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